

ELECTRONICALLY FILED ON 05 OCTOBER 2007

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of inventor(s):

Michel Luc Cote et al.

Application No. 10/799,073

Confirmation No. 8538

Filing Date: 12 March 2004

Title: Design and Layout of Phase Shifting Photolithographic Masks

Group Art Unit: 1756

Examiner: Stephen D. Rosasco

CUSTOMER NO. 30437

MAIL STOP ISSUE FEE

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

SUBMISSION OF PRIOR ART AFTER NOTICE OF ALLOWANCE

Sir:

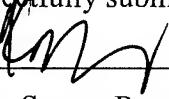
Applicants submit the below-listed prior art to be placed in the record:

- U.S. Patent No. 6,004,701 issued to Uno et al.
- U.S. Patent No. 6,391,501 issued to Ohnuma
- Japanese Publication No. 11-212247 dated 06 August 1999
- Japanese Publication No. 10-326007 dated 18 December 1998

The Commissioner is hereby authorized to charge any fee determined to be due in connection with this communication, or credit any overpayment, to our Deposit Account No. 50-0869 (NMTI 1002-26).

Dated: 5 Oct. 2007

Respectfully submitted,



Kenta Suzue Reg. No. 45,145

NUMERICAL c/o:

HAYNES BEFFEL & WOLFELD LLP

P.O. Box 366

Half Moon Bay, CA 94019

(650) 712-0340 phone

(650) 712-0263 fax